



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RD-28,484-1

SERIAL NO.

~~10/731374~~
10/731374INFORMATION DISCLOSURE STATEMENT BY APPLICANT
LIST OF ITEMSApplicant
Marc (NMN) SchaepekensFiling Date
11/27/01Group
~~1762~~ 1762



U.S. PATENT DOCUMENTS & U.S. PATENT APPLICATION PUBLICATIONS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	A1	4,871,580	10/3/89	Schram et al.		
	A2	4,957,062	9/18/90	Schuurmans et al.		
	A3	5,120,568	6/9/92	Schuurmans et al.		
	A4	6,213,049	4/10/01	Yang		
	A5					

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	B1					
	B2					

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, etc.)

	C1	"Temperature and Growth-Rate Effects on the Hydrogen Incorporation in Hydrogenated Amorphous Silicon", WMM Kessels et al., Department of Applied Physics, Eindhoven University of Technology, 1998, pp 29-33.
	C2	"Improvement of Hydrogenated Amorphous Silicon Properties With Increasing Contribution of SiH ₃ to Film Growth", WMM Kessels et al., Department of Applied Physics, Eindhoven University of technology, pp 107-110.
	C3	Application Serial No. 09/681, 820, filed June 11, 2001, "Apparatus and Method for Large Area Chemical Vapor Deposition Using Multiple Expanding Thermal Plasma Generators".
	C4	Application Serial No. 09/683,149, Specification RD-28,667 - "Apparatus and Method for Depositing Large Area Coatings on Planar Surfaces", Marc (NMN) Schaepekens.
	C5	
	C6	

EXAMINER 

DATE CONSIDERED

4/22/05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant